**ABSTRACT**

**Method for recycling a source substrate**

The present invention relates to process for recycling a source substrate (1) comprising a surface region (6) and regions (5) in relief on the surface region (6), said regions (5) in relief corresponding to residual regions of a layer (4) of the source substrate (1), said residual regions not being separated from the rest of the source substrate (1) during a prior removal step, characterized in that it comprises selective electromagnetic irradiation of the source substrate (1) at a wavelength such that the damaged material of the surface region (6) absorbs the electromagnetic irradiation.

The present invention also relates to a recycled source substrate (1) and to a process for transferring a layer (4) from a source substrate (1) recycled for this purpose.

Fig 1c.